

Claims:

1. A process chamber, comprising:
 - one or more walls defining a processing region;
 - a gas distribution plate located in the processing region, the gas distribution plate comprising:
 - a first surface; and
 - a second surface, wherein a plurality of through holes extend from the first surface to the second surface and a plurality of blind holes partially extend from the first surface; and
 - a substrate support located in the processing region,wherein the one or more walls include a side wall and a lower wall, and the process chamber further comprises a structure disposed on the side wall, wherein the structure includes a plurality of compartments, wherein each compartment of the plurality of compartments includes a gas feed, and wherein the structure includes a surface facing the gas distribution plate, and the surface is coated with a reflective or absorptive material.